

Complete set of Claims

1(original). A photosensitive composition for an interlayer insulation film, characterized by comprising: a modified polysilsesquiazane having a weight average molecular weight of 500 to 200,000 comprising basic constitutional units represented by formula $-\text{SiR}^1(\text{NR}^2)_{1.5}-$ wherein R^1 's each independently represent an alkyl group having 1 to 3 carbon atoms or a substituted or unsubstituted phenyl group; R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group, up to 50% by mole of said basic constitutional units having been replaced by a linking group other than the silazane bond; a photoacid generating agent; and a basic material.

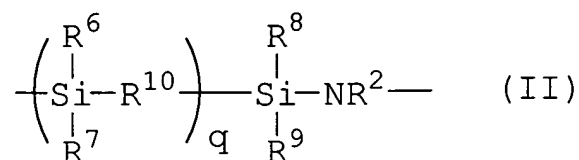
2(original). The photosensitive composition for an interlayer insulation film according to claim 1, wherein said modified polysilsesquiazane further comprises 0.1 to 100% by mole, based on said basic constitutional units, of other constitutional units represented by formulae $-\text{SiR}^3_2\text{NR}^2-$ and/or $[\text{SiR}^3_3(\text{NR}^2)_{0.5}]$ - wherein R^3 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group.

3(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 or 2, wherein said linking group is represented by formula (I):



wherein R⁴ and R⁵ each independently represent hydrogen, or an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; and p is an integer of 1 to 10.

4(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~or~~ 2, wherein said linking group is represented by formula (II):



wherein R⁶, R⁷, R⁸, and R⁹ each independently represent an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; R¹⁰ represents an oxygen atom or an alkylene, alkenylene, cycloalkylene, arylene, alkylimino, or alkylsilylene group; R²'s each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and q is an integer of 1 to 10.

5(original). The photosensitive composition for an interlayer insulation film according to claim 4, wherein R⁶, R⁷, R⁸, and R⁹ represent a methyl group, R¹⁰ represents a phenylene group, R² represents hydrogen, and q is 1.

6(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~any one of claims 1 to 5~~, wherein said photoacid generating agent is selected from the group consisting of sulfoxime compounds and triazine compounds.

7(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~any one of claims 1 to 6~~, wherein said basic material is selected from the group consisting of higher amines, hindered amines, and alkanolamines.

8(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~any one of claims 1 to 7~~, which further comprises 0.1 to 40% by mass, based on the photosensitive composition, of a dissolution preventive selected from the group consisting of t-butoxycarbonylated catechol, t-butoxycarbonylated hydroquinone, t-butyl benzophenone-4,4'-dicarboxylate, and t-butyl 4,4'-oxydibenzoate.

9(Currently Amended).The photosensitive composition for an interlayer insulation film according to claim 1 ~~any one of claims 1 to 8~~, which further comprises a nitro- or carbonic ester-containing water-soluble compound as a shape stabilizer.

10(Currently Amended). The photosensitive composition for an interlayer insulation film according to claim 1 ~~any one of claims 1 to 8~~, which further comprises a sensitizing dye.

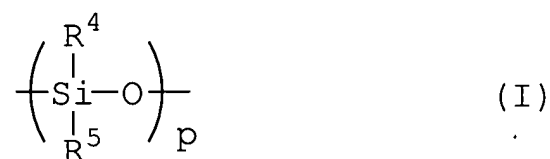
11(Original). A method for forming a patterned interlayer insulation film, characterized by comprising: forming a coating of a photosensitive composition for an interlayer insulation film, comprising a modified polysilsesquiazane, a photoacid generating agent, and a basic material, said modified polysilsesquiazane having a weight average molecular weight of 500 to 200,000 comprising basic constitutional units represented by formula $-\text{SiR}^1(\text{NR}^2)_{1.5}-$ wherein R^1 's each independently represent an alkyl group having 1 to 3 carbon atoms or a substituted or unsubstituted phenyl group, R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted

or unsubstituted phenyl group, up to 50% by mole of said basic constitutional units having been replaced by a linking group other than a silazane bond; exposing said coating pattern-wise to light; dissolving and removing the coating in its exposed area; and subjecting the residual patterned coating in an ambient atmosphere to standing or baking.

12(new) The composition according to claim 1, where the basic material is an amine.

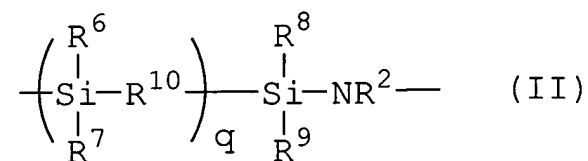
13(new). The composition according to claim 12, where the basic material is selected from an alkanol amine, hindered amine and amine containing greater than 4 carbon atoms.

14(new). The photosensitive composition for an interlayer insulation film according to claim 2, wherein said linking group is represented by formula (I):



wherein R⁴ and R⁵ each independently represent hydrogen, or an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; and p is an integer of 1 to 10.

15(new). The photosensitive composition for an interlayer insulation film according to claim 2, wherein said linking group is represented by formula (II):



wherein R^6 , R^7 , R^8 , and R^9 each independently represent an alkyl, alkenyl, cycloalkyl, aryl, aralkyl, alkylamino, alkylsilyl, or alkoxy group; R^{10} represents an oxygen atom or an alkylene, alkenylene, cycloalkylene, arylene, alkylimino, or alkylsilylene group; R^2 's each independently represent hydrogen, an alkyl group having 1 to 3 carbon atoms, or a substituted or unsubstituted phenyl group; and q is an integer of 1 to 10.